

Juan Duarte

List of Publications by Year in descending order

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papers

986

citations

516710

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times ranked

974

citing authors

#	ARTICLE	IF	CITATIONS
1	Negative Capacitance in Short-Channel FinFETs Externally Connected to an Epitaxial Ferroelectric Capacitor. <i>IEEE Electron Device Letters</i> , 2016, 37, 111-114.	3.9	198
2	BSIM6: Analog and RF Compact Model for Bulk MOSFET. <i>IEEE Transactions on Electron Devices</i> , 2014, 61, 234-244.	3.0	105
3	BSIMa€”SPICE Models Enable FinFET and UTB IC Designs. <i>IEEE Access</i> , 2013, 1, 201-215.	4.2	101
4	Engineering Negative Differential Resistance in NCFETs for Analog Applications. <i>IEEE Transactions on Electron Devices</i> , 2018, 65, 2033-2039.	3.0	79
5	Impact of Parasitic Capacitance and Ferroelectric Parameters on Negative Capacitance FinFET Characteristics. <i>IEEE Electron Device Letters</i> , 2017, 38, 142-144.	3.9	71
6	Modeling of GaN-Based Normally-Off FinFET. <i>IEEE Electron Device Letters</i> , 2014, 35, 612-614.	3.9	40
7	RF Modeling of FDSOI Transistors Using Industry Standard BSIM-IMG Model. <i>IEEE Transactions on Microwave Theory and Techniques</i> , 2016, 64, 1745-1751.	4.6	34
8	NCFET Design Considering Maximum Interface Electric Field. <i>IEEE Electron Device Letters</i> , 2018, 39, 1254-1257.	3.9	33
9	Designing 0.5 V 5-nm HP and 0.23 V 5-nm LP NC-FinFETs With Improved $\$I_{OFF}\$$ Sensitivity in Presence of Parasitic Capacitance. <i>IEEE Transactions on Electron Devices</i> , 2018, 65, 1211-1216.	3.0	31
10	Response Speed of Negative Capacitance FinFETs., 2018, ,.		29
11	Variation Caused by Spatial Distribution of Dielectric and Ferroelectric Grains in a Negative Capacitance Field-Effect Transistor. <i>IEEE Transactions on Electron Devices</i> , 2018, 65, 4652-4658.	3.0	29
12	Unified FinFET compact model: Modelling Trapezoidal Triple-Gate FinFETs., 2013, ,.		28
13	Capacitance Modeling in III-V FinFETs. <i>IEEE Transactions on Electron Devices</i> , 2015, 62, 3892-3897.	3.0	25
14	BSIM-HV: High-Voltage MOSFET Model Including Quasi-Saturation and Self-Heating Effect. <i>IEEE Transactions on Electron Devices</i> , 2019, 66, 4258-4263.	3.0	23
15	Modeling 20-nm Germanium FinFET With the Industry Standard FinFET Model. <i>IEEE Electron Device Letters</i> , 2014, 35, 711-713.	3.9	20
16	A Predictive Tunnel FET Compact Model With Atomistic Simulation Validation. <i>IEEE Transactions on Electron Devices</i> , 2017, 64, 599-605.	3.0	20
17	Thermal resistance modeling in FDSOI transistors with industry standard model BSIM-IMG. <i>Microelectronics Journal</i> , 2016, 56, 171-176.	2.0	19
18	Modeling of Advanced RF Bulk FinFETs. <i>IEEE Electron Device Letters</i> , 2018, 39, 791-794.	3.9	17

#	ARTICLE	IF	CITATIONS
19	Effect of Polycrystallinity and Presence of Dielectric Phases on NC-FinFET Variability., 2018,,.	14	
20	BSIM-IMG: Compact model for RF-SOI MOSFETs., 2015,,.	13	
21	Compact Modeling Source-to-Drain Tunneling in Sub-10-nm GAA FinFET With Industry Standard Model. IEEE Transactions on Electron Devices, 2017, 64, 3576-3581.	3.0	13
22	Modeling STI Edge Parasitic Current for Accurate Circuit Simulations. IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems, 2015, 34, 1291-1294.	2.7	11
23	Modeling of Back-Gate Effects on Gate-Induced Drain Leakage and Gate Currents in UTB SOI MOSFETs. IEEE Transactions on Electron Devices, 2017, 64, 3986-3990.	3.0	9
24	Modeling SiGe FinFETs With Thin Fin and Current-Dependent Source/Drain Resistance. IEEE Electron Device Letters, 2015, 36, 636-638.	3.9	7
25	A Unified Flicker Noise Model for FDSOI MOSFETs Including Back-bias Effect., 2018,,.		7
26	BSIM-IMG with improved surface potential calculation recipe., 2014,,.		5
27	New Mobility Model for Accurate Modeling of Transconductance in FDSOI MOSFETs. IEEE Transactions on Electron Devices, 2018, 65, 463-469.	3.0	5